ATENT COOPERATION TREAT'

From the INTERNATIONAL SEARCHING AUTHORITY

SEMICONDUCTOR ENERGY LABORATORY CO., LTD.

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PCT

WRITTEN OPINION OF THE INTERNATIONAL SEARCHING AUTHORITY (PCT Rule 43bis.1)

Date of mailing (day/month/year)

10 5 2005

Applicant's or agent's file reference

PCT7697-7698

FOR FURTHER ACTION

See paragraph 2 below

International application No. PCT/JP2005/001286 International filing date (day/month/year)

Priority date (day/month/year)

24.01.2005

26.01.2004

International Patent Classification (IPC) or both national classification and IPC

Int.Cl. G02F1/1368, 1/1343, G09F9/00, H01L21/28, 21/3205, 21/336, 29/417, 29/423, 29/49, 29/786, H05B33/14

Applicant

SEMICONDUCTOR ENERGY LABORATORY CO., LTD.

- 1. This opinion contains indications relating to the following items:
 - V Box No. I Basis of the opinion
 - Box No. II **Priority**
 - Box No. III Non-establishment of opinion with regard to novelty, inventive step and industrial applicability
 - Box No. IV Lack of unity of invention
 - Box No. V Reasoned statement under Rule 43bis.1(a)(i) with regard to novelty, inventive step or industrial applicability;

citations and explanations supporting such statement

- Box No. VI Certain documents cited
- Box No. VII Certain defects in the international application
- Box No. VIII Certain observations on the international application

2. FURTHER ACTION

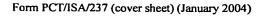
If a demand for international preliminary examination is made, this opinion will be considered to be a written opinion of the International Preliminary Examining Authority ("IPEA") except that this does not apply where the applicant chooses an Authority other than this one to be the IPEA and the chosen IPEA has notified the International Bureau under Rule 66.1bis(b) that written opinions of this International Searching Authority will not be so considered.

If this opinion is, as provided above, considered to be a written opinion of the IPEA, the applicant is invited to submit to the IPEA a written reply together, where appropriate, with amendments, before the expiration of 3 months from the date of mailing of Form PCT/ISA/220 or before the expiration of 22 months from the priority date, whichever expires later.

For further options, see Form PCT/ISA/220.

3. For further details, see notes to Form PCT/ISA/220.

| Date of completion of this opinion 18.04.200 | 05 | | | |
|--|-------------------------------|------|------|------|
| Name and mailing address of the ISA/JP | Authorized officer | · | 4L | 3239 |
| Japan Patent Office | TAKASHI WATAHIKI | | L1 | |
| 3-4-3, Kasumigaseki, Chiyoda-ku, Tokyo 100-8915, Japan | Telephone No. +81-3-3581-1101 | Ext. | 3498 | |





WRI :N OPINION OF THE INTERNATIONAL SEARCHING AUTHORITY

Inte jonal application No.
PCT/JP2005/001286

| Во | x No. I | Basis of the opinion |
|----|------------|---|
| 1. | which it | ard to the language, this opinion has been established on the basis of the international application in the language in was filed, unless otherwise indicated under this item. is opinion has been established on the basis of a translation from the original language into the following language , which is the language of a translation furnished for the purposes of international search (under illes 12.3 and 23.1(b)). |
| 2. | With reg | ard to any nucleotide and/or amino acid sequence disclosed in the international application and necessary to the nvention, this opinion has been established on the basis of: |
| | a. type of | material |
| | Г | a sequence listing |
| | Г | table(s) related to the sequence listing |
| | b. format | of material |
| | | in written format |
| | Г | in computer readable form |
| | c. time of | filing/furnishing contained in the international application as filed. |
| | Γ. | filed together with the international application in computer readable form. |
| | Γ. | furnished subsequently to this Authority for the purposes of search. |
| 3. | file | addition, in the case that more than one version or copy of a sequence listing and/or table relating thereto has been d or furnished, the required statements that the information in the subsequent or additional copies is identical to that he application as filed or does not go beyond the application as filed, as appropriate, were furnished. |
| 4. | Additiona | l comments: |
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WRIT 'N OPINION OF THE INTERNATIONAL SEARCHING AUTHORITY

Intern nal application No.

PCT/JP2005/001286

| Box No. IV | Lack of unity of invention |
|--|---|
| 1. In respo | nse to the invitation (Form PCT/ISA/206) to pay additional fees the applicant has: |
| ۲ | paid additional fees |
| r | paid additional fees under protest |
| \rightarrow | not paid additional fees |
| | Authority found that the requirement of unity of invention is not complied with and chose not to invite the applicant to additional fees. |
| 3. This Aut | hority considers that the requirement of unity of invention in accordance with Rule 13.1, 13.2 and 13.3 is |
| Г с | omplied with |
| ▽ n | ot complied with for the following reasons: |
| a first contain select forming conductions [19-25] and a | secial technical features of claims [1-18] relates to [forming st conductive pattern by discharging a conductive material ining a photosensitive material by droplet discharging; cively exposing the first conductive film pattern to laser light; ag second conductive film pattern by developing the exposed first cive pattern], while the special technical features of claims [5] relates to [a channel length of the channel formation region space between the source electrode an the drain electrode have doths that are the same as that of the gate electrode]. |
| There | is no technical relationship among those inventions involving more of the same or corresponding technical features. |
| | fore, these groups of inventions are not so linked as to form gle general inventive concept. |
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| 4. Consequ | uently, this opinion has been established in respect of the following parts of the international application: |
| Г. | all parts. |
| F t | the parts relating to claims Nos. $1-18$ |
| | |

WRI7 'N OPINION OF THE INTERNATIONAL SEARCHING AUTHORITY

Inter 'onal application No.

PCT/JP2005/001286

Box No. V Reasoned statement under Rule 43bis.1(a)(i) with regard to novelty, inventive step or industrial applicability; citations and explanations supporting such statement

| Statement | | | |
|-------------------------------|--------|------|-------|
| Novelty (N) | Claims | 1-18 | YES |
| | Claims | | NO |
| Inventive step (IS) | Claims | • | YES |
| | Claims | 1-18 | NO NO |
| Industrial applicability (IA) | Claims | 1-18 | YES |
| | Claims | | NO |

2. Citations and explanations

D1:JP 2000-258921 A (CANON KABUSHIKI KAISHA) 2000.09.22

D2:US 2002/0012868 A1(TSUYOSHI FURUSE) 2002.01.31

D3:JP 6-61257 A(DAI NIPPON PRINTING CO., LTD.) 1994.03.04

[Claims 1-4]

The subject matter of claims 1-4 does not appear to involve an inventive step with respect to D1 and D2.

D1 and D2 discloses forming a first conductive film pattern containing a photosensitive material, selectively exposing the first conductive pattern, and forming a second conductive film pattern by developing the exposed conductive film pattern.

And D2 discloses forming the first conductive pattern by droplet discharging (see paragraph [0036]).

And Exposing photosensitive material to laser light, and active matrix display device including TFT, are well known.

[Claims 5-12]

The subject matter of claims 5-12 does not appear to involve an inventive step with respect to D1 and D2.

The person skilled in the art would easily conceive the idea of applying the feature disclosed in D1 and D2 to forming a gate electrode, a source electrode and a drain electrode.

[Claims 13-18]

The subject matter of claims 13-18 does not appear to involve an inventive step with respect to D1-D3.

D3 discloses rear exposure method to pattern a resist mask for forming a source electrode and a drain electrode.

Therefore, the skilled person in the art would easily conceive the idea of applying the feature in D1 and D2 to the invention in D3.